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INTERNATIONAL ELECTROTECHNICAL COMMISSION

SEMICONDUCTOR DEVICES -

Part 14-3: Semiconductor sensors – Pressure sensors

FOREWORD

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International Standard IEC 60747-14-3 has been prepared by subcommittee 47E: Discrete semiconductor devices, of IEC technical committee 47: Semiconductor devices.

The text of this standard is based on the following documents:

FDIS Report on voting			
	$\backslash \backslash \backslash \backslash \bigcirc$	FDIS	Report on voting
47E/191/FDIS 47E/195/RVD	$\langle \cdot \rangle$	47E/191/FDIS	47E/195/RVD

Full information on the voting for the approval of this standard can be found in the report on voting indicated in the above table.

This publication has been drafted in accordance with the ISO/IEC Directives, Part 3.

A bilingual version of this standard may be issued at a later date.

The committee has decided that the contents of this publication will remain unchanged until 2006. At this date, the publication will be

- reconfirmed;
- withdrawn;
- replaced by a revised edition, or
- amended.

INTRODUCTION

This part of IEC 60747 should be read in conjunction with IEC 60747-1. It provides basic information on semiconductor

- terminology;
- letter symbols;
- essential ratings and characteristics;
- measuring methods;
- acceptance and reliability.

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SEMICONDUCTOR DEVICES –

Part 14-3: Semiconductor sensors – Pressure sensors

1 Scope

This part of IEC 60747-14 specifies requirements for semiconductor pressure sensors measuring absolute, gauge or differential pressures.

2 Normative references

The following normative documents contain provisions which, through reference in this text, constitute provisions of this part of IEC 60747-14. For dated references, subsequent amendments to, or revisions of, any of these publications do not apply. However, parties to agreements based on this part of IEC 60747-14 are encouraged to investigate the possibility of applying the most recent editions of the normative document indicated below. For undated references, the latest edition of the normative document referred to applies. Members of IEC and ISO maintain registers of currently valid International Standards.

IEC 60747-1:1983, Semiconductor devices - Discrete devices - Part 1: General

IEC 60747-14-1:2000, Semiconductor devices - Part 14-1: Semiconductor sensors – General and classification

3 Terminology and letter symbols

3.1 General terms

3.1.1 Semiconductor pressure sensors

A semiconductor pressure sensor converts the difference between two pressures into an electrical output quantity. One of the two pressures may be a reference pressure (see 3.2.3). It includes linear and on off (switch) types of sensors.

A linear sensor produces electrical output quantity changes linearly with the pressure difference.

An on-off sensor switches an electrical output quantity on and off between two stable states when the increasing or decreasing pressure differences cross given threshold values.

In this standard, the electrical output quantity is described as a voltage: output voltage. However, the statements made in this standard are also applicable to other output quantities such as those described in 3.8 of IEC 60747-14-1: changes in impedance, capacitance, voltage ratio, frequency-modulated output or digital output.

3.1.2 Sensing methods

3.1.2.1 Piezoelectric sensing

The basic principle of piezoelectric devices is that a piezoelectric material induces a charge or induces a voltage across itself when it is deformed by stress. The output from the sensor is amplified in a charge amplifier which converts the charge generated by the transducer sensor into a voltage that is proportional to the charge. The main advantages of piezoelectric sensing are the wide operating temperature range (up to 300 °C) and high-frequency range (up to 100 kHz).

3.1.2.2 Piezoresistive sensing

The basic principle of a piezoresistor is the change of the resistor value when it is deformed by stress. The sensing resistors can be either p- or n-type doped regions. The resistance of piezoresistors is very sensitive to strain, and thus to pressure, when correctly placed on the diaphragm of a pressure sensor. Four correctly oriented resistors are used to build a strain gauge in the form of a resistor bridge.

An alternative to the resistor bridge is the transverse voltage strain gauge. It is a single resistive element on a diaphragm, with voltage taps centrally located on either side of the resistor. When a current is passed through the resistor, the voltages are equal when the element is not under strain, but when the element is under strain, a differential voltage output appears.

3.1.2.3 Capacitive sensing

A small dielectric gap between the diaphragm and a plate makes a capacitance which changes with the diaphragm movement. Single capacitance or differential capacitance techniques can be used in open- or closed-loop systems. Capacitance and capacitive changes can be measured either in a bridge circuit or using switched capacitor techniques. Any of the capacitive sensing techniques used in a micromachined structure require an a.c. voltage across the capacitor being measured. Capacitive sensing has the following advantages: small size of elements, wide-operating temperature range, ease of trimming, good linearity, and compatibility to CMOS signal conditioning.

3.1.2.4 Silicon vibrating sensing

The vibrating element of a silicon micromachined structure is maintained in oscillation, either by piezoelectric or electrical field energy. The application of pressure to the silicon diaphragm produces strain on the micromachined structure and the vibration frequency is measured to determine applied pressure.

3.1.2.5 Signal conditioning

Semiconductor pressure sensors are mainly micromachined structures including a sensing element. Other electrical components or functions can be performed at the same time and in the same package on the process line. Most pressure sensors offer integrated signal conditioning.

Signal conditioning transforms a raw sensor output into a calibrated signal. This process may involve several functions, such as calibration of initial zero pressure offset and pressure sensitivity, compensation of non-linear temperature errors of offset and sensitivity, compensation of the non-linearity and output signal amplification of the pressure.

3.1.2.6 Temperature compensation

Semiconductor sensors are temperature sensitive. Some are temperature non-compensated sensors while others are compensated with added circuitry or materials designed to counteract known sources of error.

When non-compensated, the variations due to the temperature follow physical laws and a temperature coefficient (α) is representative of this physical phenomena.

When compensated, the temperature remaining error is also dependant on the way the compensation is performed. In this case, a maximum temperature deviation (Δ) better represents this error.

3.2 Definitions

For the purposes of this part of IEC 60747, the definitions in IEC 60747-1 and the following definitions apply.

3.2.1

piezoresistance coefficient

measure of the piezoresistance effect derived from the semiconductor materials under the application of strain

3.2.2

absolute pressure

pressure using absolute vacuum as the datum point

3.2.3

reference pressure

pressure against which pressures are defined, usually absolute vacuum or ambient atmospheric pressure

3.2.4

differential pressure

difference between the two (absolute) pressures that act simultaneously on opposite sides of the membrane

3.2.5

relative pressure

differential pressure when one of the two pressures is considered to be a reference pressure with respect to which the other pressure is being measured

3.2.6

gauge pressure

relative pressure when the ambient atmospheric pressure is used as the reference pressure

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system pressure (or common-mode pressure)

static pressure that acts on the sensor but does not represent the pressure to be converted, in the case of a differential pressure sensor

3.2.8

over-pressure capability

maximum pressure that may be applied to the sensor without damage or loss of calibration accuracy

3.2.9

differential output resistance

first derivative of output voltage as a function of output current at the specified pressure. Refers to a basic sensor (without integrated signal amplification)

NOTE In practice, the differential resistance value can be expressed as the quotient of the change of the output voltage over the change in output current resulting from a small change in output load resistance.

3.2.10

input resistance

supply voltage divided by the supply current

3.2.11

isolation resistance

resistance between all the connected electrical terminals of the sensor and the sensor part which is in contact with the sensed element

NOTE In practice, this is not applicable when the sensed element, such as gas or oil, is not conductive.